

(1) General:

Vintage: Nov. 2009

Wafer Size: 300mm

SW Version: 5.0.0

Main Process: Photo

Sub-Process: ARF-Scanner



(2) Hardware Configuration:

	Moudule	Check Items	Yes or No	Remarks
1	OIU	Is the motherboard complete?	✓	
2		Are the keyboard, mouse, and monitor working?	✓	
3	WH	Hardware defects or damage	X	
4		Are there any scratches or dirt on the component gripper or TSU surface?	X	
5	WS	Hardware defects or damage	X	
6		Are there any scratches or dirt on the surface of the component Closing Disk?	X	Adsorb on the lens bottom.
7		Are there any scratches or dirt on the surface of the mirror block components?	✓	A little bit of particle
8		Are there any scratches or dirt on the Z-mirror component surface?	✓	A little bit of particle E-side finger print
9		Are there any scratches or dirt on the surface of the image sensor components?	✓	A little particle, tool usage traces
10		Are there any scratches or dirt on the surface of the wafer table component?	X	A little particle
11	RH	Hardware defects or damage	X	
12	RS	Hardware defects or damage	X	
13		Are there any scratches or dirt on the R-chuck component surface?	X	
14	ILL	Hardware defects or damage	X	
15		Does the surface of the REMA lens have any scratches or dirt?	X	
16		Is there a number of Bending Points?	X	
17	Lens	Hardware defects or damage	X	
18		Are there any scratches or dirt on the top and bottom of the lens?	X	
19		Is the sensor on the top of the lens complete?	✓	

TWINSKAN XT:1700Fi SYSTEM ACCEPTANCE TESTS

Category		Items	Spec	Model: XT1700Fi
Full Acceptance Test			XT1700Fi	Result-Data
1. Overlay	1.1 Single machine overlay		≤ 5	NA
2. Intensity	2.1 Slit integrated power, 11 scans in 26mm Setting 1 [mW/cm]		≥ 1650**	NA
3. Projection Lens	3.1 RMS Z5-Z37 [nm]		≤ 1.4	2.75
	3.2 RMS Spherical [nm]		≤ 0.8	0.75
	3.3 RMS coma [nm]		≤ 0.8	0.96
	3.4 RMS astigmatism [nm]		≤ 0.8	0.85
	3.5 RMS 3-foil [nm]		≤ 0.8	0.74
	3.6 Long range straylight [SAMOS %]		≤ 0.9	NA
	3.7 Short range straylight [SAMOS %]		≤ 1.2	NA
4. Illumination	4.1 Dose system performance, setting 1 [%]		≤ 1.0	NA
	4.2 Integrated slit uniformity, setting 1 [%]		≤ 0.30	NA
	4.3 Integrated scan uniformity, setting 1 [%]		≤ 0.2	NA
	4.4 Dose repeatability [%]		≤ 0.2	NA
	4.5 Dose accuracy setting 1 [%]		± 0.7	NA
5. Pupil Verification	5.1 Ellipticity, Setting 1 [meam]		≤ 1.5	NA
	5.2 Sigma variation setting 1 [range]		≤ 0.007	NA
6. Focus and Leveling	6.1 Wafer map repeatability (99.7%) [nm]		≤ 8	NA
7. Dynamic Performance	7.1 MA X&Y (mean+3ig) [nm]		≤ 2.0	NA
	7.2 MSD X&Y (max of mean per field) [nm]		≤ 6.5	NA
	7.3 Inspection time (<200 particles found) [nm]		≤ 225	NA
	7.4 Size accuracy - lates spheres () Upper surface			
	10um [um]		± 3	NA
	30um [um]		± 3	NA
	50um [um]		± 5	NA
	7.5 Size accuracy - latex spheres () Lower surface			
	10um [um]		± 3	NA
	30um [um]		± 3	NA
50um [um]		± 5	NA	
8. BMWL - fine	Test results			NA
9. TSPE	Test results			NA
10. SWZS	Test results			NA